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(54) Title: PROCESS FOR REMOVING RESIDUES FROM A SEMICONDUCTOR SUBSTRATE

(57) Abstract

A process of treating a substrate having photoresist applied thereto, comprising the steps of: (a) removing said photoresist from said substrate by a method selected from the group consisting of photoresist stripping, plasma etch residue cleaning, or a combination thereof; and (b) rinsing said substrate with a non–corrosive rinsing composition comprising: (1) water; and (2) one or more water–soluble corrosion inhibitors selected from the group consisting essentially of hydroxylamine, at least one hydroxylammonium salt, at least one water–soluble organic acid, at least one amino acid, and combinations thereof.